

2015 IEEE International Meeting for Future of Electron Devices, Kansai

(IMFEDK 2015)

**Kyoto, Japan
4 – 5 June 2015**



**IEEE Catalog Number: CFP15567-POD
ISBN: 978-1-4799-8616-3**

The Conference Theme

New functional devices for the next generation

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(¹Osaka University, ²ROHM Co., Ltd.)

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